



## **Applied Materials' UVision Inspection System and Producer HARP CVD System Win Semiconductor International Awards**

July 3, 2006

SANTA CLARA, Calif.--(BUSINESS WIRE)--July 3, 2006--Applied Materials, Inc. (Nasdaq:AMAT) today announced that two of its products have received Semiconductor International magazine's prestigious Editors' Choice Best Product Award.

-- The Applied UVision(TM) Inspection system was recognized for helping to move wafer inspection forward into the nanomanufacturing era with breakthrough DUV(1) laser 3-D brightfield inspection technology that can find nanometer-scale defects never before detected.

-- The Applied Producer(R) HARP(TM) system plays a key role in overcoming transistor performance challenges by enabling chipmakers to boost chip speed by depositing strain inducing dielectric films in transistor structures, while also enabling geometric device scaling with unparalleled high aspect ratio gap-fill capability.

"Both of these products represent key advances in nanomanufacturing technology(TM) that are contributing to the continued progression of Moore's Law," noted Dr. Mark Pinto, senior vice president and chief technology officer of Applied Materials. "The UVision technology addresses the vital economic area of chip yield, using new technology to quickly find nano-scale killer defects. The Producer HARP system helps overcome one of chipmaking's greatest challenges, the slowing progress of transistor performance in sub-90nm designs, by offering chipmakers a cost-effective solution to fill shrinking structures with specialized dielectric materials."

With the innovative Applied UVision system, Applied Materials revolutionized defect inspection by introducing the semiconductor industry's first laser 3-D brightfield inspection tool. The UVision system addresses the critical need for significantly higher inspection sensitivity and productivity for 65nm manufacturing and beyond, featuring a production-worthy detection technology that can find many types of "killer" defects never seen before. This innovative inspection technology allows customers to rapidly resolve performance-limiting defect issues and achieve greater chip yields. For more information, please visit: [www.appliedmaterials.com/resolution](http://www.appliedmaterials.com/resolution)

The Applied Producer HARP (High Aspect Ratio Process) system is the only commercially-available, high-productivity CVD(1) technology that meets the stringent more than 7:1 high aspect ratio gap-fill requirements for STI(1) and PMD(1) applications in 65nm, 45nm and below designs. The HARP process also enables enhanced transistor performance by depositing strain-inducing films that can significantly increase drive current, without added integration complexity. For more information on the Applied Producer HARP system, visit: <http://www.appliedmaterials.com/products/harp>

Applied Materials, Inc. (Nasdaq:AMAT) is the global leader in nanomanufacturing technology(TM) solutions for the electronics industry with a broad portfolio of innovative equipment, service and software products. At Applied Materials, we apply nanomanufacturing technology to improve the way people live. Learn more at [www.appliedmaterials.com](http://www.appliedmaterials.com).

(1) DUV = deep ultraviolet; STI = shallow trench isolation; PMD = pre-metal dielectric; CVD = chemical vapor deposition

CONTACT: Applied Materials, Inc.  
Betty Newboe, 408-563-0647 (editorial/media)  
Randy Bane, 408-986-7916 (financial community)

SOURCE: Applied Materials, Inc.